Equipment for Back-end Process

Wafer to Wafer Bonding Equipment



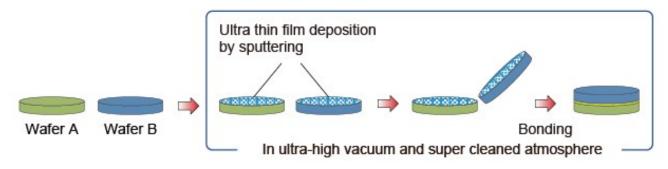


BC7000 φ100 / φ150 mm

BC7300 φ200 / φ300 mm

Features

- Bonding at room temperature
- No pressure during bonding
- · High bonding strength
- Bonding of any similar or dissimilar materials
- High throughput
- · Strong bonding by diffusion of sputtered atoms



Atomic Diffusion Bonding Process Flow

Equipment for Front-end Process

Sputtering Equipment for Memory

MTJ Sputtering Equipment for Mass production NC7900

Features

- Ultra-high vacuum and oblique angle rotation PVD
- · Fine interface control with ultra-thin multi-layers
- Compatible with Planar & Perpendicular MTJ formation

MTJ Etching Equipment for Mass production NC8000

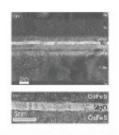
Features

- . MTJ Etching Equipmentfor Mass production
- Overall etching process by clampless holder with 2 axes of revolution and stage angle





Basic MRAM cell structure



CoFeB/MgO/CoFeB MTJ



Memory Wire Sputtering Equipment for mass production IC7500

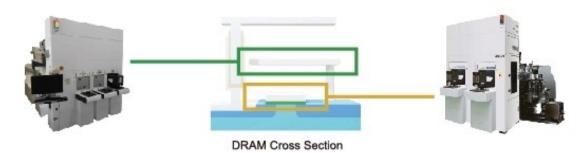
Features

- Cathode magnet position (3D) is variable in-situ per each recipe
- Provides >90% uptime rate at semiconductor memory production line. (failure rate < 1%)

Metal Gate Sputtering Equipment for mass production FC7100

Features

- Capable of controlled film composition through ultra-high vacuum co-sputtering
- High-precision control of (0.1 nm unit) film thickness and excellent uniformity (1σ < 1%)
- Low material cost through use of compact cathode.
 Easy material changeover.



Equipment for Back-end Process

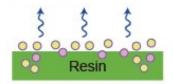
Sputtering Equipment for Advanced Packaging



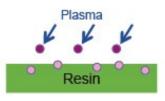
EL3400

Panel PVD system for advanced packaging applications including barrier and copper seed deposition

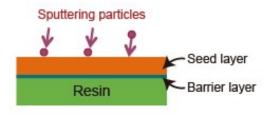
Cu seed sputter process



Low temp degas



Surface treatment



Ti/Cu metal deposition

Features

- Strong adhesion on substrate
- Available to deposit films on resin or glass substrate
- Available to handle panel size substrate

Substrates for EL3400





Interposer

